Claims

- [c1] A CVD apparatus comprising:
 - a vacuum vessel separated into two chambers; the first one of the two chambers containing a radiofrequency electrode;
 - the second one of the two chamber containing a substrate support mechanism for mounting a substrate; wherein said vacuum vessel is separated by an electrically conductive partitioning section, said partitioning section comprising:
 - a plurality of through-holes to allow communication between the first chamber and the second chamber; an interior space for receiving a reactive gas, the interior space separated from the first chamber and communicating with the second chamber through a plurality of diffusion holes; and
 - a heater for heating the electrically conductive partition section.
- [c2] The apparatus of claim 1, further comprising:
 an electrically conductive spiral shield; and
 wherein the partitioning section is mounted to the vacuum vessel by means of a mounting screw such that

electrical contact between the partitioning section and the vacuum vessel is achieved through said spiral shield.

[c3] A CVD apparatus comprising:

a vacuum vessel separated into two chambers; at least one radio-frequency electrode contained in a first one of said two chambers;

a substrate support mechanism contained in the second one of said two chambers;

an electrically conductive partition section; an electrically conductive spiral shield; and wherein said vacuum vessel is separated into two chambers by said electrically conductive partition section which is mounted to said vacuum vessel by means of a mounting screw such that electrical contact between the partitioning section and the vacuum vessel is achieved through said spiral shield.